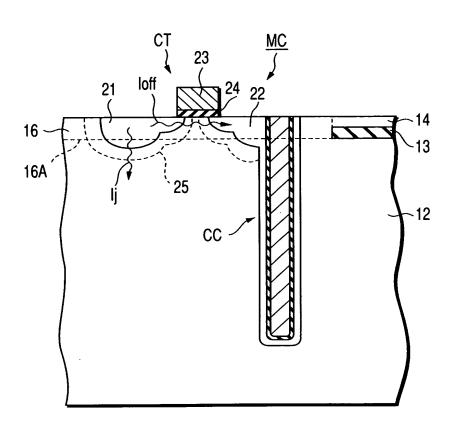
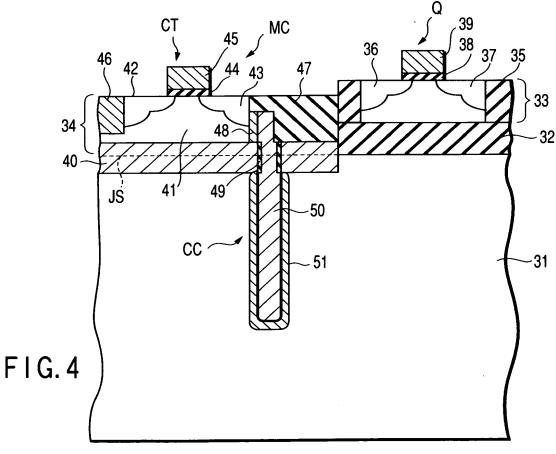
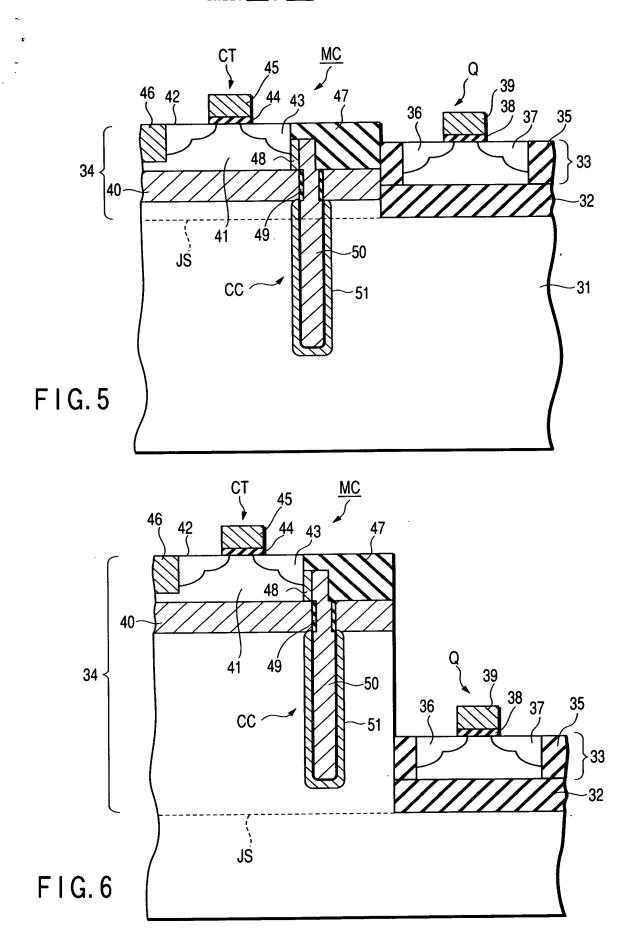
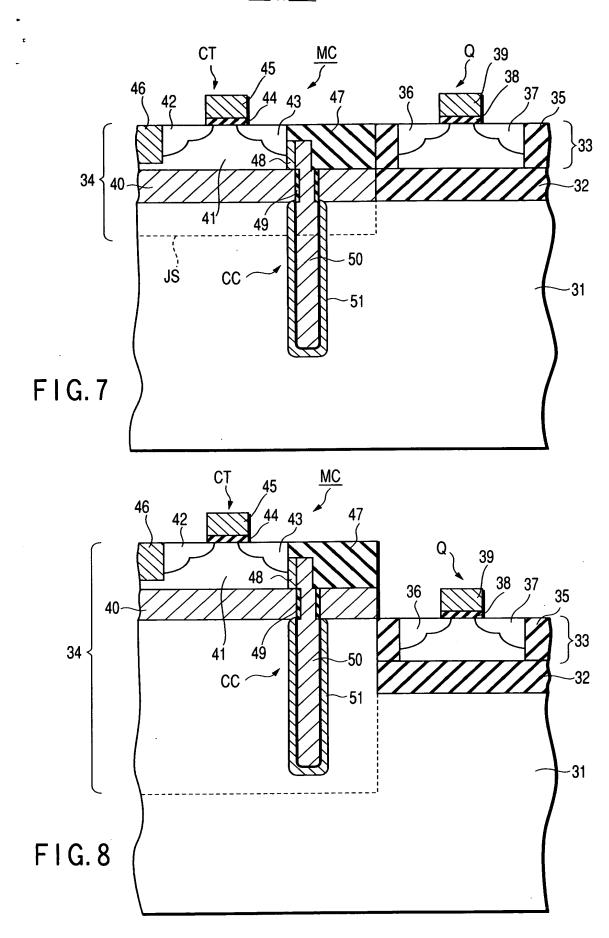


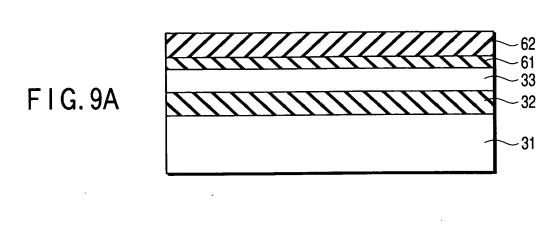
FIG. 3 PRIOR ART

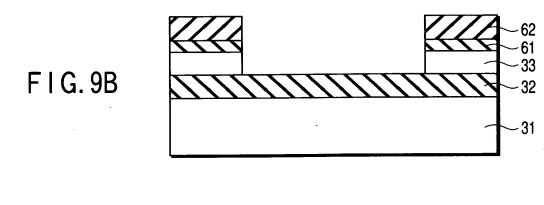


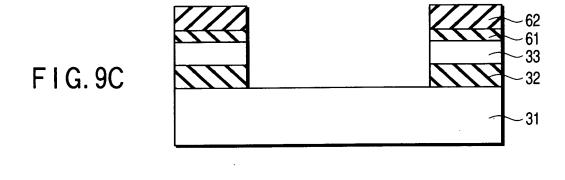


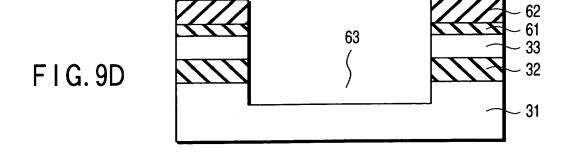


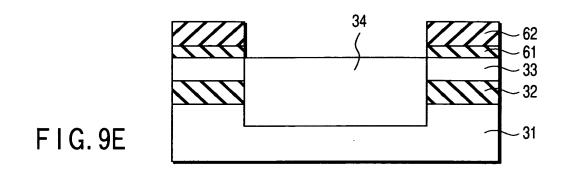


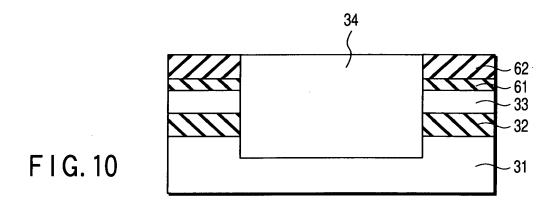


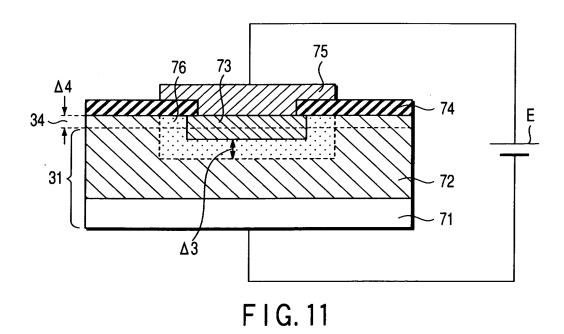


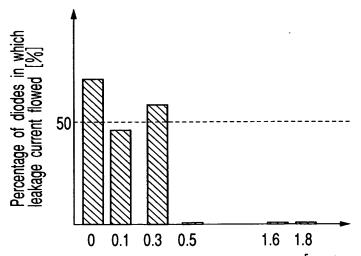






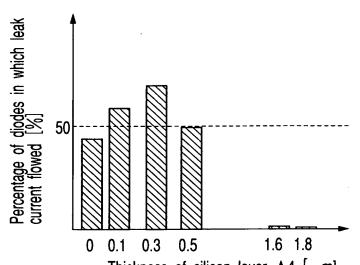






Thickness of silicon layer $\Delta 4 \ [\mu m]$ Reverse bias: 2V (Width of depletion layer $\Delta 3$: 0.25 μm)

F I G. 12



Thickness of silicon layer $\Delta 4$ [μ m] Reverse bias: 4V (Width of depletion layer $\Delta 3$: 0.4 μ m)

FIG. 13

RE1: Leakage current when thickness of silicon layer is set at 0, 0.1, 0.3 μ m

RE2: Leakage current when thickness of silicon layer is set at $0.5 \,\mu\,\mathrm{m}$

RE3: Leakage current in this embodiment (when thickness of silicon layer is set at 1.6, $1.8 \mu m$)

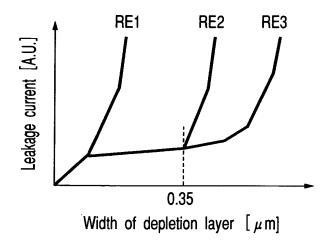


FIG. 14

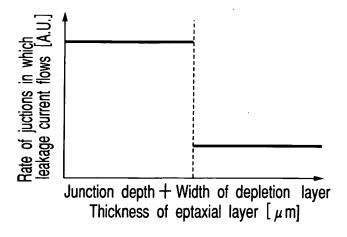
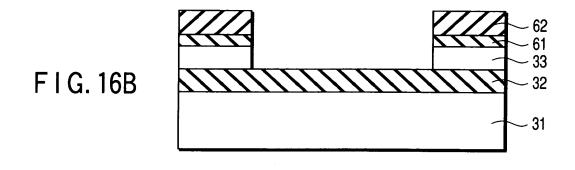
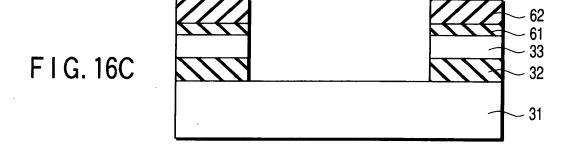


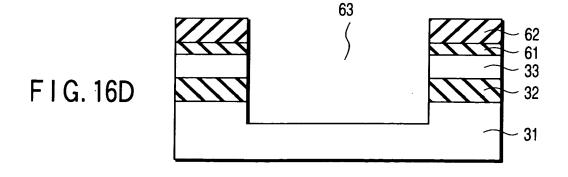
FIG. 15



FIG. 16A 33 32 31







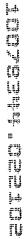




FIG. 16E

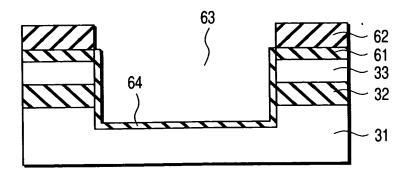


FIG. 16F

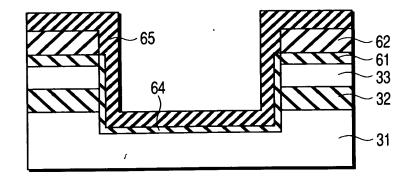


FIG. 16G

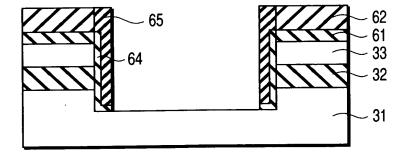
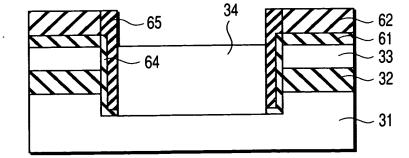


FIG. 16H





F I G. 17

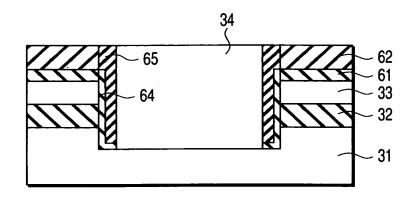
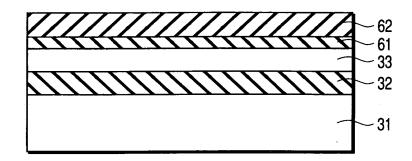


FIG. 18A



F I G. 18B

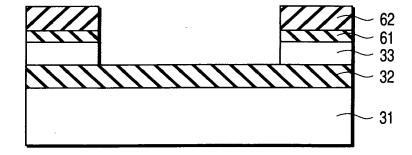
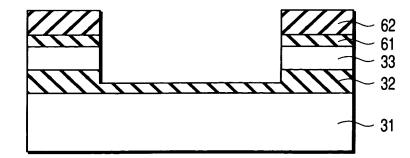


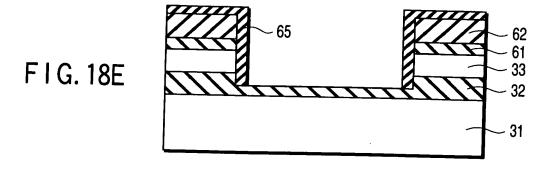
FIG. 18C

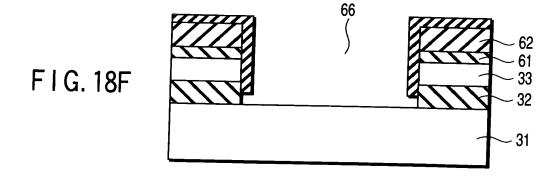


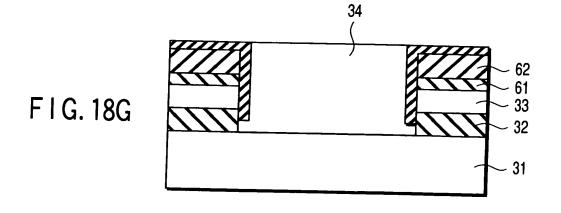




- 62 -65 61 33 FIG. 18D 32 - 31







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